| | Hits | Search Text | DBs |
|---|---|---|---|
| 22 | 38 | ((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat$4 or (spatial near14 modulat$4) or SLM or deflect$4 or acousto$6) and ((immers$4 near12 (liquid or fluid)) same (inlet or outlet or port or input or output or passag$5) same (lens or optic or illuminat$4 or project$4)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 23 | 52 | ((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive) same (immersion near6 (fluid or liquid))) and ((immers$4 near12 (liquid or fluid)) near18 (inlet or outlet or port or input or orifice or output or passag$5) near28 (lens or optic or illuminat$4 or project$4)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |

| | Hits | Search Text | DBs |
|---|---|---|---|
| 24 | 120 | ((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive) same (immersion near6 (fluid or liquid))) and ((immers$4 near12 (liquid or fluid)) same (inlet or outlet or port or input or output or passag$5) same (lens or optic or illuminat$4 or project$4)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |